

REMARKS:

The Examiner has rejected claims 1-12, 16 and 19 under 35 USC 112 for failing to comply with the written description requirement, and for failing to comply with the enablement requirement. More particularly, the Examiner has objected to the language in claim 1 which recites that at least one of the AP pinned layer structure and the free layer are formed by a process other than ion beam deposition. The Applicant has amended claim 1 in order to remove elements that the Examiner states are not supported by the written description.

In addition, the Examiner has rejected claim 19 as adding new matter, because of the use of the word "wafer". The Applicant has amended claim 19 to recite that the ion assist source (IAD) is directed at a "substrate" rather than a wafer. Support for this amendment can be found on page 16, lines 7-9. Language similar to that of claim 19 has been added to claim 16 as well.

The Applicant sincerely believes that the remaining claims are in condition for allowance. A notice of allowance is, therefore, respectfully requested. In the event a telephone conversation would expedite the prosecution of this application, the Examiner may reach the undersigned at (408) 971-2573. For payment of any additional fees due in connection with the filing of this paper, the Commissioner is authorized to charge such fees to Deposit Account No. 50-2587 (Order No. HSJ920030150US1).

Respectfully submitted,

By: /Ronald B. Feece/

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